A nisotropy of superconductivity of as-grown M gB₂ thin lm s by m olecular beam epitaxy

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Abstract

Superconducting thin $\ln s$ of m agnesium diboride (M gB₂) were prepared on M gO (001) substrate by a molecular beam epitaxy (M BE) method with the co-evaporation conditions of low deposition rate in ultra-high vacuum. The structural and physical properties of the $\ln s$ were studied by RHEED, XRD, XPS, resistivity and m agnetization measurements. All $\ln s$ demonstrated superconductivity without use of any post-annealing process. The highest T_{c;on set} determined by resistivity measurement was about 33K in the present samples. A nisotropic superconducting properties were evaluated by the resistivity and magnetic measurements. We will discuss the anisotropy of superconductivity for as-grow n M gB₂ thin $\ln s$. The discovery of superconductivity at 39K in m agnesium diboride (M gB₂) has attracted great interest in science and technology since it shows the highest transition temperature (T_c) among interm etallic compounds [1]. There have already been several reports on the preparation technique of M gB₂ thin Im so far 2, 3]. M any of them require a post-annealing process to in prove their physical properties and attain superconductivity. A s-grown process without the use of any post-annealing process is strongly desired for the fabrication of tunnelling junctions and multilayers. Several groups have reported as-grown superconducting M gB₂ thin Im so far 4, 5, 6]. In as-grown m ethod, low temperature synthesis, is needed to depress high volatility of M g, m akes di cult to produce M gB₂ thin Im with high crystallinity. It is considered that M gB₂ needs to be grown up in vacuum as high as possible to get good crystallinity, because the quality of M gB₂ thin Im is considerably a ected by residual gases [7]. This m ethod is a promising way for device application. Therefore, it is desired to establish the low rate deposition technique at low growth temperature to produce high quality Im s.

The evaluation of the anisotropy in superconducting materials is very in portant not only for the basic understanding of this material but also for its potential applications because anisotropy strongly a ects the ux pinning, critical currents, and electronic device limit. Since M gB₂ consists of alternating hexagonal layers of M g atom s and graphite-like honeycom b layers of B atom s, electronic anisotropy has been predicted by theoretical calculations [8, 9]. However, only few indirect measurements have been made to determ ine the anisotropy, e.g., on single crystal [10], and c-axis oriented thin lm s of M gB₂ [11]. The anisotropy ratio, $= H_{C 2pc}(0)/H_{C 2pb}(0)$, were reported as 2.6 and 1.8-2.0, respectively.

We reported previously the synthesis of thin \ln by molecular beam epitaxy (MBE) in the co-evaporation conditions of low grow th tem perature, low deposition rates and ultra high vacuum [12]. In this paper, we present the optimizing of the co-evaporation conditions for as-grown superconducting thin \ln of MgB₂ using co-evaporation method. And an isotropic superconducting properties were evaluated by the resistivity and magnetic measurements.

The M gB₂ In s were grown on M gO (001) substrates in an M BE chamber with a base pressure of 4 10 ¹⁰ Torr. Pure m etal of M g and B were used as the evaporation sources. The both purities of M g and B were 3N . M g was evaporated from a K nudsen cell, and B by electron-beam . The deposition rate was controlled by a quartz-crystal m onitor (Q CM) with the ix ratio of M g to B varied from 9 to 10 times as high as the nominal ux ratio to compensate M g loss. The deposition rate of B was varied from 0.5A /sec to 0.3A /sec. The thickness of Im swas typically 1000A. The grow th temperature (T_S) was varied from 300 C to 200 C . The background pressure during the grow th was better than 4 10 ¹⁰ Torr. A ll of the Im swere covered by 50A -thick M g cap layer to avoid oxidation. The crystal structure was characterized by in-situ re ection high-energy electron di raction (RHEED) and exsitu X -ray di raction (KRD:2 scan). The resistivity and m agnetic susceptibility m easurem ents were carried out by the standard four-probe technique and SQUID m agnetom eter, respectively.

RESULTS AND DISCUSSION

We exam ined the characteristics of a thin $\ln m$ ade under a range of deposition conditions on a M gO (001) substrate. Firstly, we exam ined M gB₂ thin $\ln s m$ ade by using a relatively low deposition temperature of 100-300 C. The deposition rate of B was xed at 0.5A/sec. Figure 1 (a) shows the resistivity as a function of temperature curve of the M gB₂ thin $\ln s$ grown at 200 C and 250 C with an M g/B ratio of 9-10. The T_{cyonset}-T_{cyoffset} was 33.1-31.1K and 31.3-28.3K, respectively. Here, T_{cyonset} was de ned as the temperature at resistance abruptly to drop, and the T_{cyoffset} was de ned as the temperature at which resistivity reached zero. The norm all state resistivity at room temperature (RT) was 159.5 (250 C) and 93.1 cm (200 C), respectively. It should be marked that the resistivity of the $\ln s$ grown at 200 C is lower than those of at 250 C. This result can be ascribed to the reduction of grain boundary, that is, enlargement of grain size.

The dcm agnetic properties were measured with a superconducting quantum interference device magnetom eter (MPM S-5, Quantum design) at an applied eld perpendicular to the

In plane. The size of sam ples was 3 3m m². Figure 1 (b) shows the tem perature dependence of the zero-eld-cooled and eld-cooled dc magnetization (M-T) curves of the M gB₂ thin Im s grown at 200 C and 250 under a eld of 1m T. The M-T curves exhibit the T_c around 26K (250 C) and 31K (200 C), where the grow th tem perature are designated in parenthesis.

Figure 2 shows the substrate tem perature (T_s) dependence of the T_c. Between 200 C and 250 C, the lms showed superconducting transition above 30K, whereas that m ade at 300 C showed no superconductivity. This indicates that the grow th tem perature lim it is 300 C for the as-grown superconducting M gB₂ thin lms by these co-evaporation conditions. From these results, we have chosen the typical grow th conditions as $T_s = 200$ C.

To establish optim al conditions, we studied the dependence of B deposition rate on the Improperties. In this series of Ims, the growth temperature was xed at 200C. The B deposition rate was decreased from 0.5 to 0.1A/sec to get lower vacuum conditions. The Mg/B ratio was xed at 9-10.

Figure 3 (a) shows the resistivity as a function oftem perature curve at various B deposition rates. The T_{conset} - $T_{coffset}$ was 31.3-28.1K (0.5A/sec), 32.6-31.9K (0.3A/sec) and 30.6-26.2 (0.1A/sec), respectively. The parenthesis mean the B deposition rates. The transition width (T_c) at 0.3A/sec had a very low value of 0.7K. In 0.1A/sec, a clear step like transition were found. This pattern suggests that the possibility of two di erent M gB₂ phase exists in this Im.

Figure 3(b) shows the M-T curves, which B deposition rate was 0.3 and 0.5A/sec. The M-T curves exhibit the T_c around 30K. As these results, the quality and superconducting properties of M gB₂ thin lm made at 0.3A/sec were improved than other deposition rate

In s. Therefore, we have chosen the typical grow th conditions; B deposition rate: 0.3A /sec.

Next, we studied anisotropy of superconductivity of as-grown M gB₂ thin $\ln . N \, \text{ew}$ $\ln w$ as prepared at T_s= 200, B deposition rate of 0.3A /sec and M g deposition rate of around 3A /sec. The structure and crystallinity were characterised by RHEED and XRD.Figure 4 (a) shows the XRD pattern of the M gB₂ thin $\ln . XRD$ results show the (001) di raction peak of the M gB₂. The RHEED pattern showed a ring pattern. The composition of the

In swas investigated by XPS.From the XPS depth proleshown in Figure 5, it was found that a MgB₂ thin In is slightly Mg decient (i.e., 25.0% Mg and 71.3% B).

The dc magnetic properties were studied with a superconducting quantum interference device magnetom eter (MPM S-5. Quantum Design) at an applied eld parallel (Hkc) or the

perpendicular to the lm plane (H kab). Figure 6(a) shows M-T curves of the M qB₂ thin

In under a eld of Im T along the perpendicular to the Im plane. The M -T curves exhibit the same superconducting transition temperature of T_c around 31K. The magnetization of the thin Im, as a function of an applied eld up to 3T (M -H curve), was measured at several temperatures. Figure 6 (b) shows the M -H curves at 5K for applied elds up to 3T at H kc and H kab. They show the typical hysteresis loop, indicating the characteristic curve of type-II superconductors. M -H curves exhibit a remarkable anisotropy between parallel and perpendicular to the Im plane.

To estimate the critical current density (J_c), we measured M +H curves of the same samples as a function of temperature. The J_c was calculated based on the Bean model [13], $J_c = 30 \text{ mV}^{-1} \text{r}^{-1}$, where m is the width of the hysteresis loop, V is the lm volume, and r is the sample halfwidth. At zero eld, the $J_{c,\infty}$ was estimated to be 7.1 $10^7 \text{A}/\text{cm}^2$ at 5K and 5.1 $10^7 \text{A}/\text{cm}^2$ at 20K, respectively from the M +H curves of Hkc. The $J_{c,\text{rab}}$ was 4.7 $10^6 \text{A}/\text{cm}^2$ at 5K and 3.2 $10^6 \text{A}/\text{cm}^2$ at 20K, respectively from the M +H curves of Hkc. The grain size.

Figure 7 shows the tem perature dependence of the resistivity under the selected m agnetic elds up to 14T for H kc and H kab. The $T_{C,onset}$ is estimated to be 31.2K at 0T, which is consistent with the result of M -T m easurements. The transition width gradually becomes broader with increasing magnetic eld from about 1K in 0T to 6.0K in 12T. This broadening is smaller compared to previous reported one of M gB₂ wires [14], bulk samples [15], or thin

lm s ⊅].

From the M-H curves, the lower critical elds, H_{C1} for H kc and H kab, were de ned by the magnetic elds where the initial slope of M_{up} curve meets the extrapolated curve of $(M_{up} + M_{down})/2$. The temperature dependence of H_{C1} is plotted as shown in Figure 8. Extrapolation of the plot to zero temperature gives the $H_{C1,c}(0)$ values of 14m T. This $H_{C1}(0)$ gives the penetration depth of 21.7nm at zero temperature based on G inzburg-Landau (GL) formulas, $H_{C1} = 0/2^2$.

The H_{C2} for H kc and H kab, were determined by the resistive onset temperature in the Figure 7. The H_{C2} (T) curves for H kc and H kab show a linear behavior in the temperature region far from T_{C} . These results give an approximate slope at T_{C} of $dH_{C2}/dT = 0.61$ (perpendicular) and 1.1 (parallel) T/K determined from the onset. Therefore, a linear extrapolation to zero

tem perature gives the $H_{C2,c}(0)$ and $H_{C2,ab}(0)$ values of 19.6T and 34.5T, respectively. A ssum ing the dirty lim it of the type-II superconductor, the $H_{C2}(0)$ values [16] is expressed as $H_{C2}(0) 0.691$ jH_{C2}/dT j T_C. Thus, $H_{C2,c}(0)$ and $H_{C2,ab}(0)$ are estimated to be 13.2T and 23.6T, respectively. The present values of $H_{C2}(0)$ in M gB₂ thin lm s are larger than previous ones, for example, grown by the two-step method β] and reported as-grown method β]. U sing the anisotropic GL formulas: $H_{C2,c} = /(2_{ab}^{2})$ and $H_{C2,ab} = /(2_{ab}^{2})$, the GL coherence length $_{c}(0)$ and $_{ab}(0)$ at zero temperature were calculated to be 2.8nm and 5.0nm, respectively. These values are larger than the typical values observed for high-temperature superconductors (HTS) and comparable to those estimated from the high-pressure sintered polycrystalline sample [1] and single crystal [10]. From the upper critical eld H_{C2} , the anisotropy ratio [= $H_{C2,ab}(0)/H_{C2,c}(0)$] was estimated to be 1.78, that is an anisotropy of the coherence length $_{ab}(0)/_{c}(0)$ 1.78. This value of is comparable to the reported value of 1.8-2.0 for the c-axis oriented M gB₂ thin lm s by two-step method [1]. The important physical values, $H_{C2,c}$, J_{c} , $H_{C1,c}$, and of our lm s are summerized in Table 1.

In sum m ary, we have grown the as-grown M gB₂ thin $\ln \operatorname{son} M$ gO (001) substrate by M BE in the conditions of low temperature, low deposition rate and ultra-high vacuum. Currently, B deposition rate is 0.3A /sec and grow th temperature is 200 C are best conditions to m ake the high quality M gB₂ thin \ln . The $\ln \operatorname{s}$ exhibit clear (001) peaks of M gB₂. However, the composition is not yet good enough to get perfectly stoichiom etric $\ln \operatorname{s}$. A superconducting transition with the onset temperature around 32K was con rm ed through the resistivity and m agnetization m easurements. We evaluated upper critical eld anisotropy ratio of as-grown M gB₂ thin $\ln \operatorname{s}$ for the rst time. The upper critical eld anisotropy ratio of as-grown M gB₂ thin $\ln \operatorname{s}$ = $\operatorname{H}_{C 2;cb}(0)/\operatorname{H}_{C 2;c}(0)$ of 1.78, was estimated from the magnetic

eld-tem perature phase diagram for the st time. The observed anisotropy is comparable to the values observed for $M gB_2$ thin lm s by two-step m ethod and single crystal These results demonstrated that this as-grown $M gB_2$ thin lm using M BE would be promising for the device application.

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H _{C2} ;c		19 . 6T
H _{C2;ab}		34 . 5T
H _{C2;c} (dirty lim it)		13 . 2T
H _{C2;ab} (dirty lim it)		23 . 6T
_c (0)		2 . 8nm
_{ab} (0)		5 . 0nm
J _{C ;c} (5K)	7.1	10^{7} A = cm ²
J _{C ;ab} (5K)	4.7	10^{6} A=cm ²
H _{Cl;c}		14m T
с		21 . 7nm

TABLE I: Superconducting properties of as-grown M gB $_2$ thin $\ \mbox{ In s in this work}$

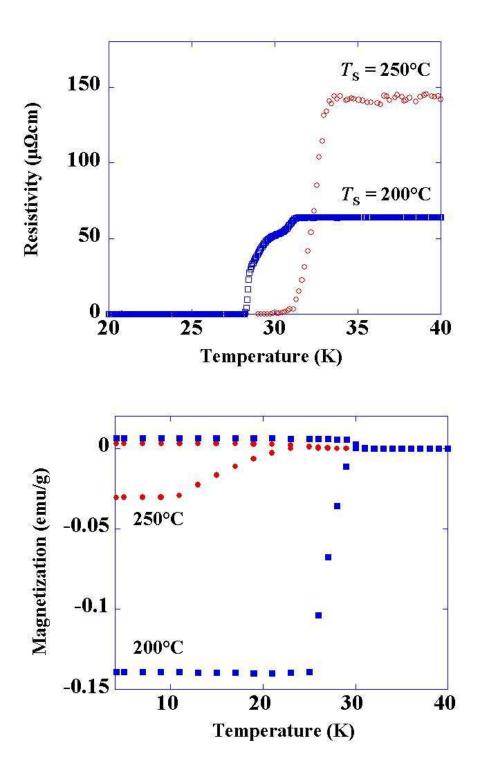


FIG.1: (a) Resistivity as a function of temperature of $M \ gB_2$ thin $\ln s \ grown$ at 250 C and 200. (b) M agnetization of these $\ln s$ as a function of temperature after cooling under zero eld and under a eld of $\ln T$.

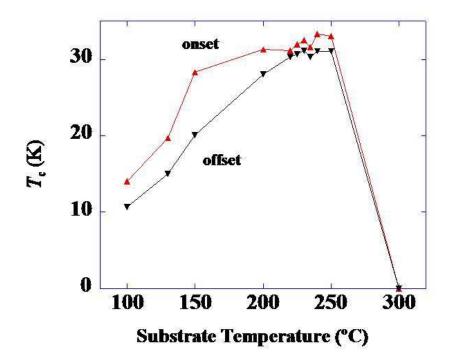


FIG.2: Substrate tem perature dependence of critical tem perature. B deposition rate: 0.5A/sec, M g deposition rate: 4.3A/sec

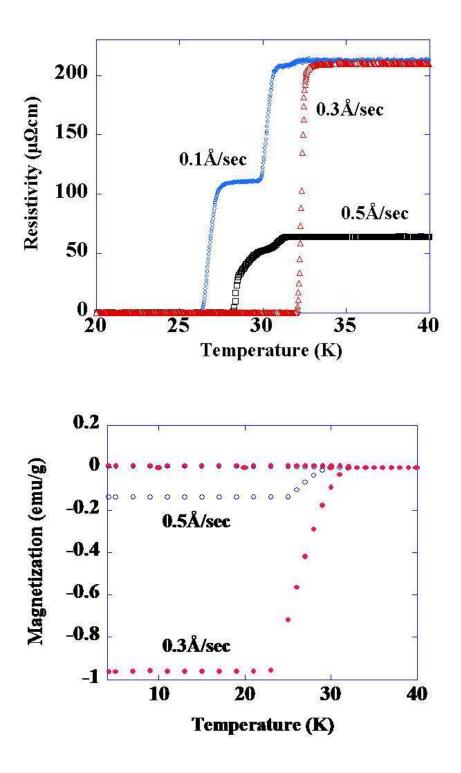


FIG.3: (a) Resistivity as a function of temperature of M gB_2 thin lm s under B deposition rates of 0.1, 0.3 and 0.5A/sec. Substrate temperature was xed at 200 C. (b) M agnetization as a function of temperature under B deposition rate 0.3 and 0.5A/sec.

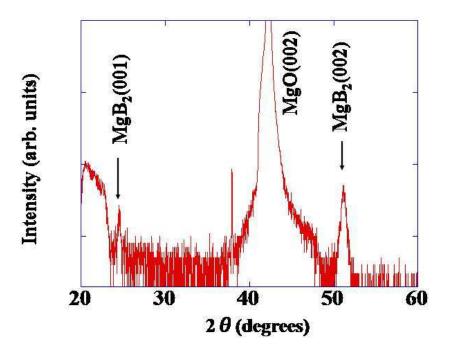


FIG.4: (a) XRD pattern for $M gB_2$ thin In s grown on M gO (001) substrate.

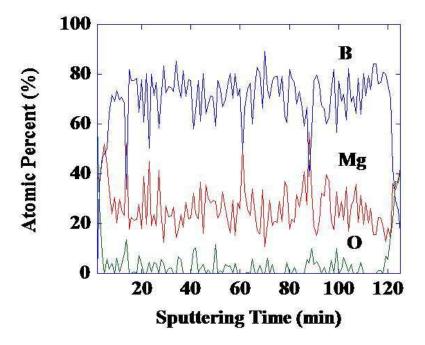


FIG.5: XPS depth pro les of a M $gB_2~$ lm , M g-cap layer was deposited on the surface M gB_2 thin lm s.

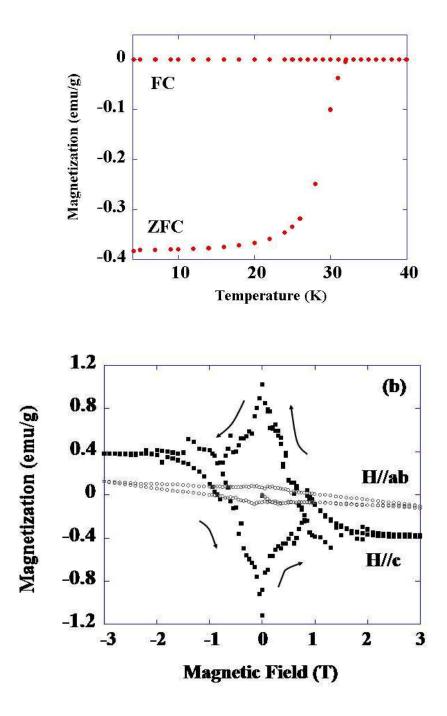


FIG.6: M agnetic properties of the M gB_2 thin lm. (a) M agnetization as a function of tem perature after cooling under zero eld and under a eld of lm T at H kc. (b) M agnetization as a function of applied elds up to 3T at 5K for H kc and H kab.

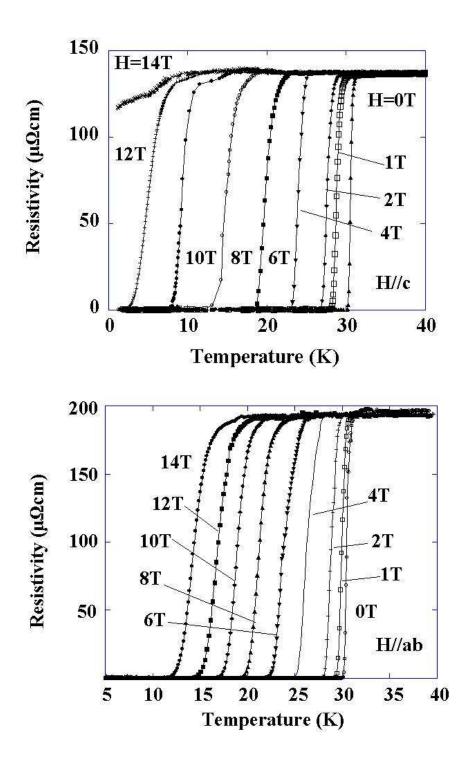


FIG. 7: Resistivity as a function of temperature under selected magnetic elds up to 14T for (a) H kc and (b) H kab.

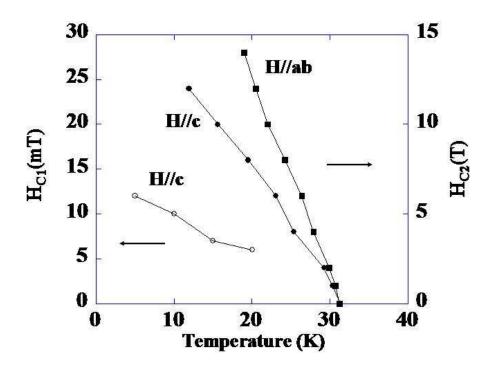


FIG.8: Magnetic eld-tem perature phase diagram of the as-grown $M gB_2$ thin lm determined our transport and magnetization experiments.